<u>AMENDMENTS TO THE CLAIMS</u>:

Please cancel Claims 1 through 8 without prejudice or disclaimer of subject matter.

Please add Claims 9 through 17 as follows:

1-8.   (Cancelled)

9.   (New) A position detection method of detecting a position of a mark, said method comprising steps of:

detecting light from the mark under a first detecting condition to obtain a position of the mark as a first position;

detecting light from the mark under a second detecting condition different from the first detecting condition to obtain a position of the mark as a second position;

obtaining offset data for offsetting one of the first and second positions based on previously prepared information for relating the first and second positions to the offset data; and

detecting a position of the mark based on the offset data and one of the first and second positions.

10.   (New) A method according to Claim 1, wherein the first and second detecting conditions differ from each other in focus state of an image of the mark.

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11.   (New) A position detection method according to Claim 1, wherein the first and second detecting conditions differ from each other in a coherence factor of an illumination optical system for illuminating the mark.

12.   (New) A position detection method according to Claim 1, wherein the first and second detecting conditions differ from each other in numerical aperture of an optical system for detecting the mark.

13.   (New) A position detection method according to Claim 1, wherein the first and second detecting conditions differ from each other in at least one of polarization and wavelength of the light from the mark.

14.   (New) A position detection method according to Claim 1, wherein the previously prepared information relates a difference between the first and second positions to the offset data.

15.   (New) A position detection method according to Claim 14, wherein the previously prepared information is a coefficient multiplied to the difference, and one of the first and second position is offset by a product of the coefficient and the difference to detect the position of the mark.

16. (New) An exposure apparatus for transferring a pattern to a workpiece, said apparatus comprising:

means for detecting light from a mark on the workpiece under a first detecting condition to obtain a position of the mark as a first position;

means for detecting light from the mark under a second detecting condition different from the first detecting condition to obtain a position of the mark as a second position;

means for obtaining offset data for offsetting one of the first and second positions based on previously prepared information for relating the first and second positions to the offset data;

means for detecting a position of the mark based on the offset data and one of the first and second positions; and

means for aligning the workpiece based on the position of the mark detected by said position detecting means.

17. (New) A device manufacturing method comprising steps of:

transferring a pattern to a workpiece using an exposure apparatus as defined in claim 16; and

developing the workpiece to which the pattern has been transferred.